

## **Amendments to the Specification**

*Please replace the paragraph on page 1, lines 5-8 with the following paragraph:*

### **1. Field of the Invention**

The present invention relates generally to an improved chemical vapor deposition process apparatus, and particularly to a process chemical vapor deposition apparatus for the deposition of tungsten silicide from dichlorosilane (DCS), ~~and an apparatus for performing the same.~~